

Patent Abstracts of Japan

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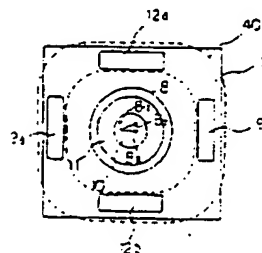
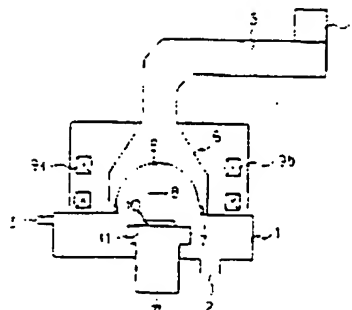
APPLICATION DATE : 20-12-88
APPLICATION NUMBER : 63322529

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TITLE : PLASMA PROCESSING DEVICE.



ABSTRACT : PURPOSE: To enhance the plasma processing ability by generating a parallel rotary mag. field on the oversurface of a specimen to undergo plasma processing, and introducing microwaves vertically to this plane of mag. field.
CONSTITUTION: In a chamber 8 a specimen 10 is placed on a lower electrode 11. Coils 9a, 9b are arranged while pinching this chamber 8, and a mag. field B_9 is generated. Also pinching the chamber 8, coils 12a, 12b are arranged, and another mag. field B_{12} is generated. These coil 12a, 12b are arranged perpendicular to the first named coils 9a, 9b, and a rotary mag. field is formed by these four coils on the oversurface of the specimen 10. Through a wave guide pipe 5, microwaves generated by a microwave oscillator 4 are introduced vertically to the plane of this rotary mag. field. This generates electro-spinning resonance state on the surface of specimen to lead to enhancement of the plasma processing ability.

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